

**Search Notes**

Application/Control No.

10/660,697

Applicant(s)/Patent under  
ReexaminationCHAMNESS, KEVIN  
ANDREW

Examiner

Jeffrey R. West

Art Unit

2857

**SEARCHED**

Class	Subclass	Date	Examiner
702	33,35,57, 58,81,113 182,183	6/24/2005	JRW
702	189-191	6/24/2005	JRW
702	194, 196	6/24/2005	JRW
702	197	6/24/2005	JRW
700	108	6/24/2005	JRW

**INTERFERENCE SEARCHED**

Class	Subclass	Date	Examiner

**SEARCH NOTES  
(INCLUDING SEARCH STRATEGY)**

	DATE	EXMR
Online Search IEEE Xplore	6/15/2005	JRW
((principal or principle) adj component adj (analysis or analyses)) and (semiconductor or semiconductors) with (manufacture	6/15/2005	JRW
or manufactures or manufacturing or manufactured or process or processes))	6/15/2005	JRW
(adaptive or recursive) with (((principal or principle) adj component adj (analysis or analyses)) or PCA)	6/15/2005	JRW
((principal or principle) adj component adj (analysis or analyses)) and (scale or scales or scaling or scaled) same centers	6/21/2005	JRW
or centered or centering or center) and (hotelling or (q adj statistic))	6/21/2005	JRW
((((principal or principle) adj component adj (analysis or analyses)) or pca) same ((scale or scales or scaling or scaled) wit	6/24/2005	JRW
adjust or adjusts or adjusting or adjusted or adjustment or adjustments)	6/24/2005	JRW